

ABSTRACT OF THE DISCLOSURE

An apparatus that includes a pumping plate having a skirt, where the skirt contains a number of holes and a wafer access slot, and where the number of holes are sized and positioned to provide uniform heating of a susceptor.

1. An apparatus for heating a susceptor, comprising:
a. a pumping plate having a skirt;
b. a number of holes in the skirt;
c. a wafer access slot in the skirt;
d. the number of holes sized and positioned to provide uniform heating of a susceptor.